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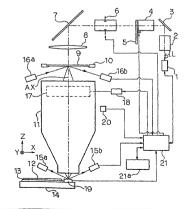
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(54) Title: METHOD OF ADJUSTING OPTICAL PROJECTION SYSTEM

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(57) Abstract

A method of adjusting an optical projection system is provided, in which the relation (dependence) between the amount of change in imaging characteristics of the optical projection system and the change in the installation environment can be measured in a short time without changing the installation environment (e.g., atmospheric pressure) of the optical projection system. Light (IL) from a light source (1) illuminates a reticle (9) through fly-eye lenses (2,4) and a condenser lens (8), and the pattern image of the reticle (9) is projected to a wafer (12) through an optical projection system (11). Since the change in wavelength of the light (IL) and the change in ambient pressure (substantially equal to atmospheric pressure) are substantially equivalent as viewed from the optical projection system (11), the atmospheric dependence of the imaging characteristic is measured by measuring the amount of change in the imaging characteristic while varying the wavelength of the light (IL).



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